Table of Contents

Introduction 1

1.1 Vapor Phase Synthesis of Materials 1
1.2 Applications Motivating Vapor Phase Process Development 3
1.3 Goals of the Dissertation 6

Background 10

2.1 Vapor Creation Using an Electron Beam Gun 12
2.1.1. Pure metal / metal alloy processing 12
2.1.2. Compound processing 16
2.1.3. Vacuum regime 17
2.2 Vapor Transport 20
2.2.1. High vacuum vapor transport 21
2.2.1.1 Spatial distribution
2.2.1.2 Angular distribution
2.2.1.3 Kinetic energy
2.2.1.4 Deposition efficiency
2.2.2. Modification of vapor transport characteristics 26
2.2.2.1 Spatial distribution
2.2.2.2 Angular distribution
2.2.2.3 Kinetic energy
2.2.2.4 Deposition efficiency
2.2.2.5 Evaporated material form
2.2.3. Jet Vapor Deposition^{TM} 34
2.2.4. Supersonic gas jet structure 37
2.2.5. Vapor transport modeling 39
2.3 Vapor Adsorption and Diffusion on a Substrate 46
2.4 Summary 49

Invention of Directed Vapor Deposition 50

DVD System Design 56

4.1 Electron Beam Gun 57
4.1.1. Maximum e-beam gun power requirements 57
4.1.2. Accelerating voltage selection 60
4.1.3. Selection of an e-beam generation source 63
4.1.4. A modified e-beam deflection system was required 65
4.1.5. Final e-beam gun configuration 68
4.2 Processing Chamber 69

4.2.1. X-ray shielding for system user protection 70
4.2.2. The chamber could accommodate various sources and substrates 72
4.3 Crucible 74
4.4 Gas System 76
4.5 Vacuum Pumps 81
4.6 Vacuum Gauges 82
4.7 Substrate Temperature Control System 83
4.8 Computer Control Methodology 84
4.9 Concluding Remark 88

Experimental Investigation of Vapor Transport 90

5.1 Overview 90
5.2 Accessible Processing Regime 91
5.3 Visual Observations of Gas Stream 97
5.4 Gas Flow / Vapor Stream / Substrate Interactions 102
5.4.1. Carrier gas flux 103
5.4.2. Mach number 106
5.4.3. Carrier gas type / e-beam power 109
5.4.4. Carrier gas flux / vapor stream interaction with substrate / crucible . . 112
5.5 Concluding Remarks 115

Materials Synthesis Via Directed Vapor Deposition 116

6.1 Overview 116
6.2 Contamination Study of Nonreactive Deposition 117
6.3 Study of Silicon Deposition 119
6.4 Study of Reactive Deposition 126
6.5 Concluding Remarks 128

Experimental Investigations of Deposition Efficiency 129

7.1 Overview 129
7.2 Deposition Efficiency Experimental Procedures 131
7.3 Flat Substrate Results 132
7.3.1. Carrier gas flux / Mach number 133
7.3.1.1 Vapor transport visualizations help explain efficiency results
7.3.1.2 A discussion of evaporation rate variations
7.3.1.3 Deposited film appearance, adhesion depend on process conditions
7.3.1.4 A summary of initial deposition efficiency results
7.3.2. E-beam power (evaporation rate effects) 142
7.3.2.1 Low beam power experiments generate inconsistent results
7.3.2.2 Visual inspection of films revealed chamber pressure and beam power effects

7.3.2.3 A summary of evaporation rate results
7.3.3. Crucible to nozzle separation effects 147
7.3.3.1 Initial vapor distribution effects upon deposition efficiency
7.3.3.2 Summary of nozzle position experiments
7.4 Fiber Substrates 151
7.4.1. Fiber coating deposition efficiency trends mirror flat substrate results 152
7.4.2. Non line-of-sight deposition enhances deposition efficiency 155
7.4.3. Inspection of coated fiber characteristics 155
7.4.4. Summary of fiber coating study 157
7.5 Clustering 158
7.5.1. Clustering probabilities for various process conditions 160
7.5.2. Ionization effects upon cluster formation probability 163
7.6 Summary 164

Vapor Transport Model Development 166

8.1 Direct Simulation Monte Carlo (DSMC) Modeling of the Flowfield 168
8.1.1. Selection of discrete atom modeling method 168
8.1.2. Adaptation of DSMC code to DVD 170
8.2 Biatomic Collision Theory (BCT) Modeling of Vapor Transport 177
8.2.1. Initial conditions 178
8.2.2. Distance between collisions 181
8.2.3. Calculation of the directed momentum transfer cross-section (σ_d) . . . 183
8.2.4. Determination of the range of atomic interaction (b_{max}) 186
8.2.5. Collision event 191
8.3 Summary 196

Vapor Transport Model Verification 198

9.1 Verification of DSMC Results 198
9.2 BCT Model Verification 200
9.2.1. Random walk 201
9.2.2. Atomic energy loss 205
9.3 Summary 211

Vapor Transport Modeling of DVD 212

10.1 Vapor Transport Predictions 213
10.1.1. Model predicts redirection at lower pressures than experiments 216
10.1.2. Dissipation of jet's fast flow limits vapor direction to substrate 217
10.1.3. Adatom kinetic energies are below initial evaporation energies 218
10.1.4. Adatom angle of incidence determined by gas near the substrate 220
10.1.5. Flowfield temperature and pressure 221
10.2 Vapor Deposition Predictions 223

10.2.1. Model predicted deposition efficiency trends 223
10.2.2. Vapor concentration effects 226
10.2.3. Predicted efficiencies 226
10.2.4. Deposition energy distributions change little with process conditions 227
10.2.5. Deposition angle distributions 228
10.2.6. Deposition distribution. 229
10.3 Summary 231

DVD System Development 234

11.1 Reconfiguration of the Gun, Vapor Source, and Carrier Gas Flow 235
11.1.1. Justification for system reconfiguration. 235
11.1.2. Model-based analysis of system reconfiguration. 237
11.2 Substrate Bias 242
11.3 Experimental Work 243
11.4 Model Development.....245
11.5 Concluding Remarks.....248

Discussion 249

12.1 Focus, Efficiency, and Angular Distribution.....250
12.2 Non-line-of-sight Coating.....251
12.3 Vapor Stream Mixing.....253
12.4 Enhanced Energy Deposition.....253
12.5 Rapid, Continuous Processing of Pure Materials and Compounds 255
12.6 Other Applications.....256
12.7 Other System Configurations.....257
12.8 Summary 257

Conclusions 258

13.1 Specific Conclusions.....259
13.2 Final Thought.....262

References 263

Appendix A - DVD Specifications 276

A.1 E-beam Gun Design Drawings 276
A.2 Processing Chamber Design Drawings.....281
A.3 Water-Cooled Crucible Design Drawings.....282
A.4 Processing Chamber Pumping Capacity Design Calculations 283

Appendix B - Clustering Calculations 286

Appendix C - Flowfield Modeling Code 287

Appendix D - Atom Tracking Code 329

Appendix E - E-beam Vapor Distribution 348